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# MOS IC Fabrication Formulas

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# List of 15 MOS IC Fabrication Formulas

## MOS IC Fabrication

### 1) Acceptor Dopant Concentration

$$fx \quad N_a = \frac{1}{2 \cdot \pi \cdot L_t \cdot W_t \cdot [\text{Charge-e}] \cdot \mu_p \cdot C_{dep}}$$

[Open Calculator !\[\]\(a870788d6ed9b8fd294b7654a8c8526b\_img.jpg\)](#)

ex

$$1E^{32} \text{electrons/m}^3 = \frac{1}{2 \cdot \pi \cdot 3.2\mu\text{m} \cdot 5.5\mu\text{m} \cdot [\text{Charge-e}] \cdot 400\text{m}^2/\text{V}^*\text{s} \cdot 1.4\mu\text{F}}$$

### 2) Body Effect in MOSFET

$$fx \quad V_t = V_{th} + \gamma \cdot \left( \sqrt{2 \cdot \Phi_f + V_{bs}} - \sqrt{2 \cdot \Phi_f} \right)$$

[Open Calculator !\[\]\(6a9b39b98eb945faa14c645ec99e4eaa\_img.jpg\)](#)

$$ex \quad 3.962586\text{V} = 3.4\text{V} + 0.56 \cdot \left( \sqrt{2 \cdot 0.25\text{V} + 2.43\text{V}} - \sqrt{2 \cdot 0.25\text{V}} \right)$$

### 3) Channel Resistance

$$fx \quad R_{ch} = \frac{L_t}{W_t} \cdot \frac{1}{\mu_n \cdot Q_{on}}$$

[Open Calculator !\[\]\(f1c5da15572e3e09d343161be98f508d\_img.jpg\)](#)

$$ex \quad 3.463203\Omega = \frac{3.2\mu\text{m}}{5.5\mu\text{m}} \cdot \frac{1}{30\text{m}^2/\text{V}^*\text{s} \cdot 0.0056\text{electrons/m}^3}$$



4) Critical Dimension 

$$fx \quad CD = k_1 \cdot \frac{\lambda_1}{NA}$$

[Open Calculator !\[\]\(cbe80b694ebd74fcfe136a095b608235\_img.jpg\)](#)


$$ex \quad 485.1883nm = 1.56 \cdot \frac{223nm}{0.717}$$

5) Depth of Focus 

$$fx \quad DOF = k_2 \cdot \frac{\lambda_1}{NA^2}$$

[Open Calculator !\[\]\(3e2231b1ad3ca8da8658228c00dd08e0\_img.jpg\)](#)

$$ex \quad 1.301331\mu m = 3 \cdot \frac{223nm}{(0.717)^2}$$

6) Die Per Wafer 

$$fx \quad DPW = \frac{\pi \cdot d_w^2}{4 \cdot S_d}$$

[Open Calculator !\[\]\(0d5ec72f61334709c3fc9450209b754f\_img.jpg\)](#)

$$ex \quad 803.2481 = \frac{\pi \cdot (150mm)^2}{4 \cdot 22mm^2}$$

7) Donor Dopant Concentration 

$$fx \quad N_d = \frac{I_{sat} \cdot L_t}{[Charge-e] \cdot W_t \cdot \mu_n \cdot C_{dep}}$$

[Open Calculator !\[\]\(b64b40baaee5acddc1eab8538ba84754\_img.jpg\)](#)

$$ex \quad 1.7E^{23} \text{electrons}/m^3 = \frac{2.015A \cdot 3.2\mu m}{[Charge-e] \cdot 5.5\mu m \cdot 30m^2/V*s \cdot 1.4\mu F}$$




8) Drain Current of MOSFET at Saturation Region 

$$\text{fx } I_d = \frac{\beta}{2} \cdot (V_{gs} - V_{th})^2 \cdot (1 + \lambda_i \cdot V_{ds})$$

Open Calculator 


$$\text{ex } 0.013718\text{A} = \frac{0.0025\text{S}}{2} \cdot (2.45\text{V} - 3.4\text{V})^2 \cdot (1 + 9 \cdot 1.24\text{V})$$

9) Drift Current Density due to Free Electrons 

$$\text{fx } J_n = [\text{Charge-e}] \cdot n \cdot \mu_n \cdot E_i$$

Open Calculator 

$$\text{ex } 53.83313\mu\text{A} = [\text{Charge-e}] \cdot 1\text{E}^6\text{electrons/cm}^3 \cdot 30\text{m}^2/\text{V}^*\text{s} \cdot 11.2\text{V/m}$$

10) Drift Current Density due to Holes 

$$\text{fx } J_p = [\text{Charge-e}] \cdot p \cdot \mu_p \cdot E_i$$

Open Calculator 

$$\text{ex } 0.071778\text{A/mm}^2 = [\text{Charge-e}] \cdot 1\text{E}^{20}\text{electrons/m}^3 \cdot 400\text{m}^2/\text{V}^*\text{s} \cdot 11.2\text{V/m}$$

11) Equivalent Oxide Thickness 

$$\text{fx } \text{EOT} = t_{\text{high-k}} \cdot \left( \frac{3.9}{k_{\text{high-k}}} \right)$$

Open Calculator 

$$\text{ex } 14.66814\text{nm} = 8.5\text{nm} \cdot \left( \frac{3.9}{2.26} \right)$$



## 12) Maximum Dopant Concentration

$$\text{fx } C_s = C_o \cdot \exp\left(-\frac{E_s}{[\text{BoltZ}] \cdot T_a}\right)$$

[Open Calculator !\[\]\(e2376d476d06eb31946dc01a69a4403a\_img.jpg\)](#)

$$\text{ex } 4.9\text{E}^{-9}\text{electrons/cm}^3 = 0.005 \cdot \exp\left(-\frac{1\text{E}^{-23}\text{J}}{[\text{BoltZ}] \cdot 24.5\text{K}}\right)$$

## 13) MOSFET Unity-Gain Frequency

$$\text{fx } f_t = \frac{g_m}{C_{gs} + C_{gd}}$$

[Open Calculator !\[\]\(0b5e7e25e8775f7e7e80906ada4f0021\_img.jpg\)](#)

$$\text{ex } 37.41497\text{kHz} = \frac{2.2\text{S}}{56\mu\text{F} + 2.8\mu\text{F}}$$

## 14) Propagation Time

$$\text{fx } T_p = 0.7 \cdot N \cdot \left(\frac{N+1}{2}\right) \cdot R_m \cdot C_l$$

[Open Calculator !\[\]\(bd3b31712ad9bab5a241210fa6925cdd\_img.jpg\)](#)

$$\text{ex } 0.778203\text{s} = 0.7 \cdot 13 \cdot \left(\frac{13+1}{2}\right) \cdot 542\Omega \cdot 22.54\mu\text{F}$$



15) Switching Point Voltage [Open Calculator](#) **fx**

$$V_s = \frac{V_{dd} + V_{tp} + V_{tn} \cdot \sqrt{\frac{\beta_n}{\beta_p}}}{1 + \sqrt{\frac{\beta_n}{\beta_p}}}$$

**ex**

$$19.15938V = \frac{6.3V + 3.14V + 25V \cdot \sqrt{\frac{18}{6.5}}}{1 + \sqrt{\frac{18}{6.5}}}$$



## Variables Used

- $C_{dep}$  Depletion Layer Capacitance (Microfarad)
- $C_{gd}$  Gate Drain Capacitance (Microfarad)
- $C_{gs}$  Gate Source Capacitance (Microfarad)
- $C_l$  Load Capacitance (Microfarad)
- $C_o$  Reference Concentration
- $C_s$  Maximum Dopant Concentration (Electrons per Cubic Centimeter)
- $CD$  Critical Dimension (Nanometer)
- $d_w$  Wafer Diameter (Millimeter)
- $DOF$  Depth of Focus (Micrometer)
- $DPW$  Die Per Wafer
- $E_i$  Electric Field Intensity (Volt per Meter)
- $E_s$  Activation Energy for Solid Solubility (Joule)
- $EOT$  Equivalent Oxide Thickness (Nanometer)
- $f_t$  Unity Gain Frequency in MOSFET (Kilohertz)
- $g_m$  Transconductance in MOSFET (Siemens)
- $I_d$  Drain Current (Ampere)
- $I_{sat}$  Saturation Current (Ampere)
- $J_n$  Drift Current Density due to Electrons (Microampere)
- $J_p$  Drift Current Density due to Holes (Ampere per Square Millimeter)
- $k_1$  Process Dependent Constant
- $k_2$  Proportionality Factor
- $k_{high-k}$  Dielectric Constant of Material



- $L_t$  Transistor's Length (Micrometer)
- $n$  Electron Concentration (Electrons per Cubic Centimeter)
- $N$  Number of Pass Transistors
- $N_a$  Acceptor Dopant Concentration (Electrons per Cubic Meter)
- $N_d$  Donor Dopant Concentration (Electrons per Cubic Meter)
- $NA$  Numerical Aperture
- $p$  Hole Concentration (Electrons per Cubic Meter)
- $Q_{on}$  Carrier Density (Electrons per Cubic Meter)
- $R_{ch}$  Channel Resistance (Ohm)
- $R_m$  Resistance in MOSFET (Ohm)
- $S_d$  Size of Each Die (Square Millimeter)
- $T_a$  Absolute Temperature (Kelvin)
- $t_{high-k}$  Thickness of Material (Nanometer)
- $T_p$  Propagation Time (Second)
- $V_{bs}$  Voltage Applied to Body (Volt)
- $V_{dd}$  Supply Voltage (Volt)
- $V_{ds}$  Drain Source Voltage (Volt)
- $V_{gs}$  Gate Source Voltage (Volt)
- $V_s$  Switching Point Voltage (Volt)
- $V_t$  Threshold Voltage with Substrate (Volt)
- $V_{th}$  Threshold Voltage with Zero Body Bias (Volt)
- $V_{tn}$  NMOS Threshold Voltage (Volt)
- $V_{tp}$  PMOS Threshold Voltage (Volt)
- $W_t$  Transistor's Width (Micrometer)
- $\beta$  Transconductance Parameter (Siemens)





















- $\beta_n$  NMOS Transistor Gain
- $\beta_p$  PMOS Transistor Gain
- $\gamma$  Body Effect Parameter
- $\lambda_i$  Channel Length Modulation Factor
- $\lambda_l$  Wavelength in Photolithography (Nanometer)
- $\mu_n$  Electron Mobility (Square Meter per Volt per Second)
- $\mu_p$  Hole Mobility (Square Meter per Volt per Second)
- $\Phi_f$  Bulk Fermi Potential (Volt)



## Constants, Functions, Measurements used

- **Constant: pi**, 3.14159265358979323846264338327950288  
*Archimedes' constant*
- **Constant: [BoltZ]**, 1.38064852E-23  
*Boltzmann constant*
- **Constant: [Charge-e]**, 1.60217662E-19  
*Charge of electron*
- **Function: exp**, exp(Number)  
*n an exponential function, the value of the function changes by a constant factor for every unit change in the independent variable.*
- **Function: sqrt**, sqrt(Number)  
*A square root function is a function that takes a non-negative number as an input and returns the square root of the given input number.*
- **Measurement: Length** in Micrometer ( $\mu\text{m}$ ), Nanometer (nm), Millimeter (mm)  
*Length Unit Conversion* 
- **Measurement: Time** in Second (s)  
*Time Unit Conversion* 
- **Measurement: Electric Current** in Ampere (A), Microampere ( $\mu\text{A}$ )  
*Electric Current Unit Conversion* 
- **Measurement: Temperature** in Kelvin (K)  
*Temperature Unit Conversion* 
- **Measurement: Area** in Square Millimeter ( $\text{mm}^2$ )  
*Area Unit Conversion* 
- **Measurement: Energy** in Joule (J)  
*Energy Unit Conversion* 
- **Measurement: Frequency** in Kilohertz (kHz)  
*Frequency Unit Conversion* 
- **Measurement: Capacitance** in Microfarad ( $\mu\text{F}$ )  
*Capacitance Unit Conversion* 



- **Measurement: Electric Resistance** in Ohm ( $\Omega$ )  
*Electric Resistance Unit Conversion* 
- **Measurement: Electric Conductance** in Siemens (S)  
*Electric Conductance Unit Conversion* 
- **Measurement: Wavelength** in Nanometer (nm), Micrometer ( $\mu\text{m}$ )  
*Wavelength Unit Conversion* 
- **Measurement: Surface Current Density** in Ampere per Square Millimeter ( $\text{A}/\text{mm}^2$ )  
*Surface Current Density Unit Conversion* 
- **Measurement: Electric Field Strength** in Volt per Meter (V/m)  
*Electric Field Strength Unit Conversion* 
- **Measurement: Electric Potential** in Volt (V)  
*Electric Potential Unit Conversion* 
- **Measurement: Mobility** in Square Meter per Volt per Second ( $\text{m}^2/\text{V}\cdot\text{s}$ )  
*Mobility Unit Conversion* 
- **Measurement: Electron Density** in Electrons per Cubic Meter ( $\text{electrons}/\text{m}^3$ ),  
Electrons per Cubic Centimeter ( $\text{electrons}/\text{cm}^3$ )  
*Electron Density Unit Conversion* 



## Check other formula lists

- [MOS IC Fabrication Formulas](#) 
- [Schmitt Trigger Formulas](#) 

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